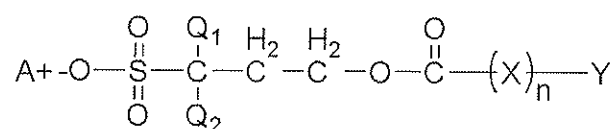


# ABSTRACT

## PHOTOACID GENERATOR, METHOD FOR MANUFACTURING THE SAME, AND RESIST COMPOSITION COMPRISING THE SAME

There are provided a photoacid generator, a method for manufacturing the same, and a resist composition comprising the same. The photoacid generator is a compound represented by the following formula 1:

[Formula 1]



wherein in the formula 1, Y represents any one selected from the group consisting of a cycloalkyl group having 3 to 30 carbon atoms, and a cycloalkenyl group having 3 to 30 carbon atoms; Q<sub>1</sub> and Q<sub>2</sub> each independently represent a halogen atom; X represents any one selected from the group consisting of an alkanediyl, an alkenediyl, NR', S, O, CO and combinations thereof; R' represents any one selected from the group consisting of a hydrogen atom and an alkyl group; n represents an integer from 0 to 5; and A<sup>+</sup> represents an organic counterion.

The photoacid generator can produce, at the time of exposure, an acid which has a low diffusion rate, has a short diffusion distance, and exhibits an appropriate degree of acidity so that the line width roughness (LWR) characteristics can be improved, and elution of which in a solvent such as pure water that is used in the process can be controlled.